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**Lin et al.**

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(54) **SEMICONDUCTOR DEVICE AND RELATED FABRICATION METHODS**

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USPC ..... 257/565, 589; 438/335  
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(\*) Notice: Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 0 days.

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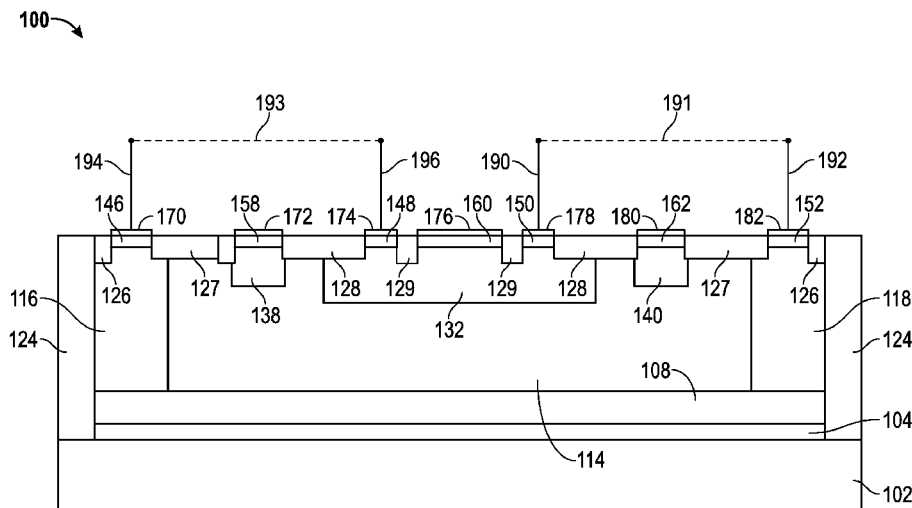
(57) **ABSTRACT**

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**H01L 29/66** (2006.01)  
**H01L 29/73** (2006.01)  
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**H01L 29/06** (2006.01)

Semiconductor device structures and related fabrication methods are provided. An exemplary semiconductor device structure includes a collector region of semiconductor material having a first conductivity type, a base region of semiconductor material within the collector region, the base region having a second conductivity type opposite the first conductivity type, and a doped region of semiconductor material having the second conductivity type, wherein the doped region is electrically connected to the base region and the collector region resides between the base region and the doped region. In exemplary embodiments, the dopant concentration of the doped region is greater than a dopant concentration of the collector region to deplete the collector region as the electrical potential of the base region exceeds that of the collector region.

(52) **U.S. Cl.**  
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**19 Claims, 9 Drawing Sheets**



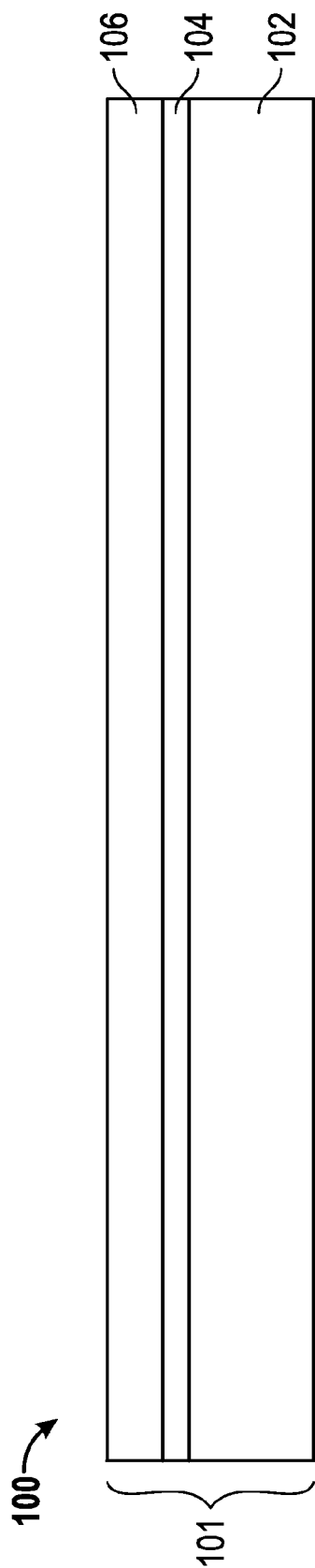


FIG. 1

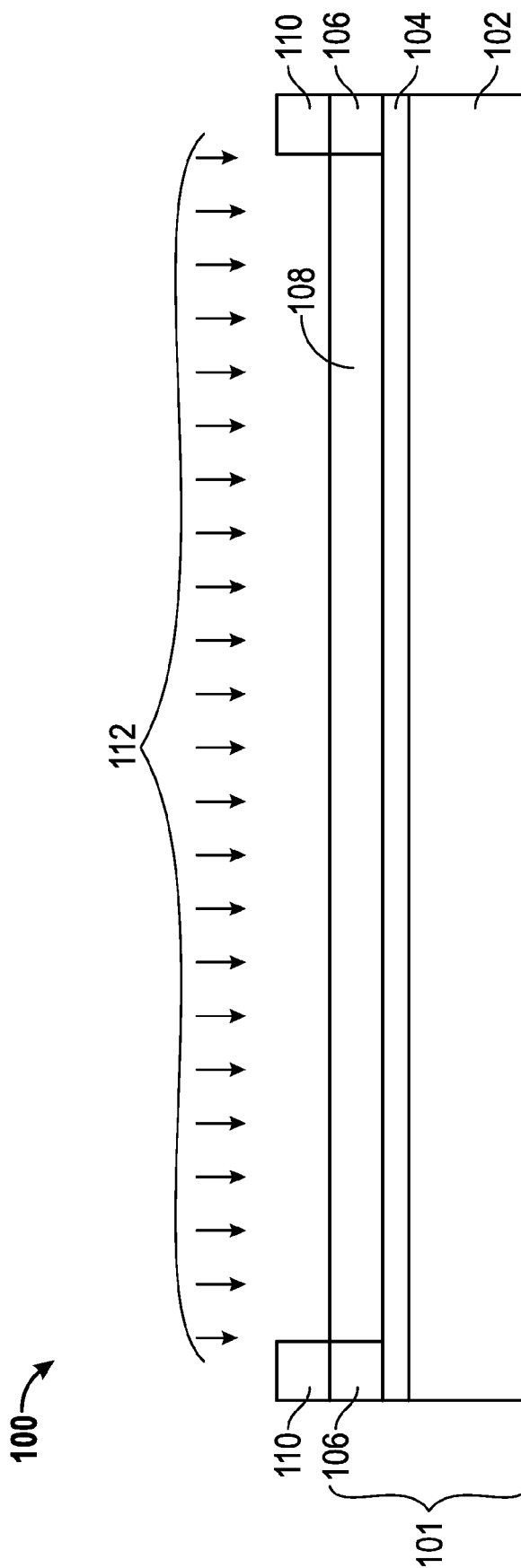


FIG. 2

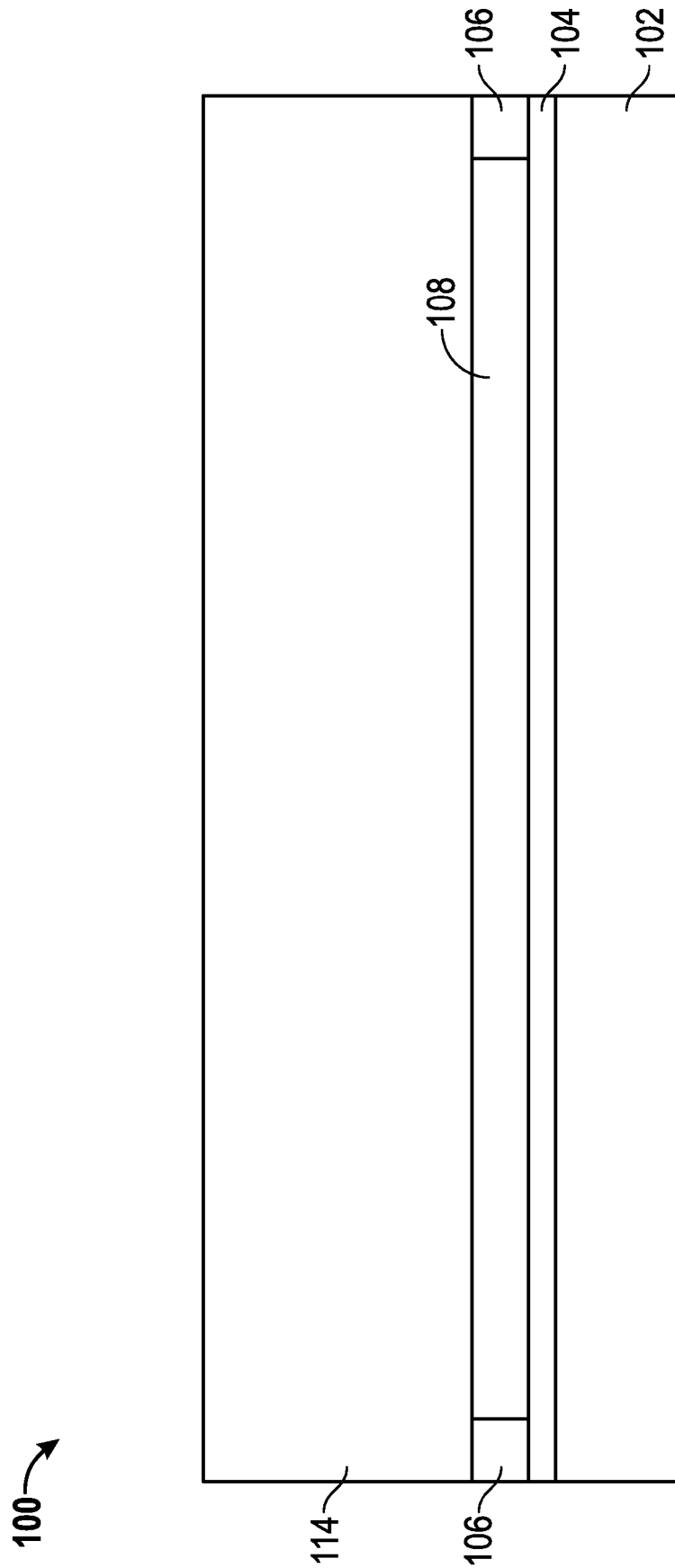


FIG. 3

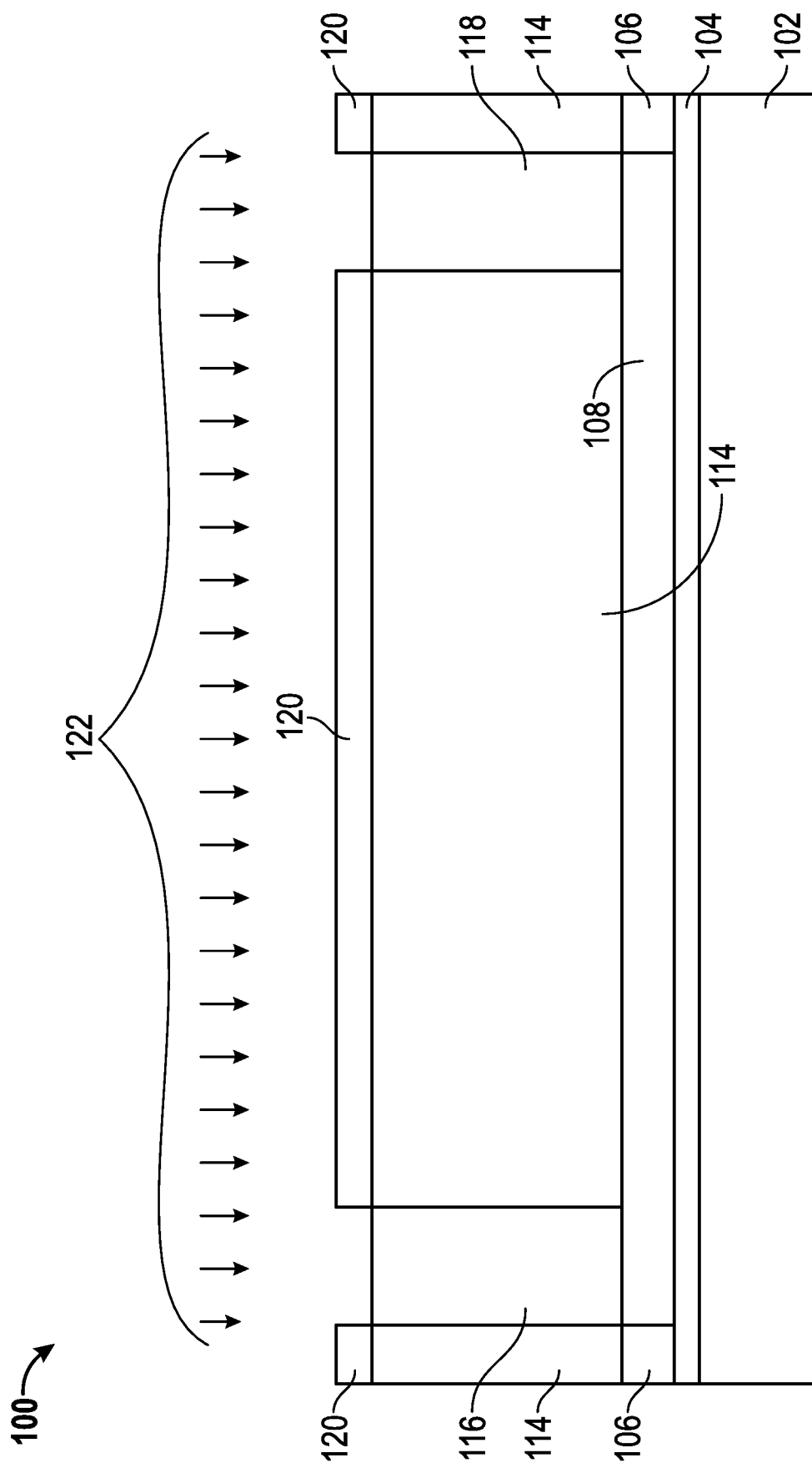


FIG. 4

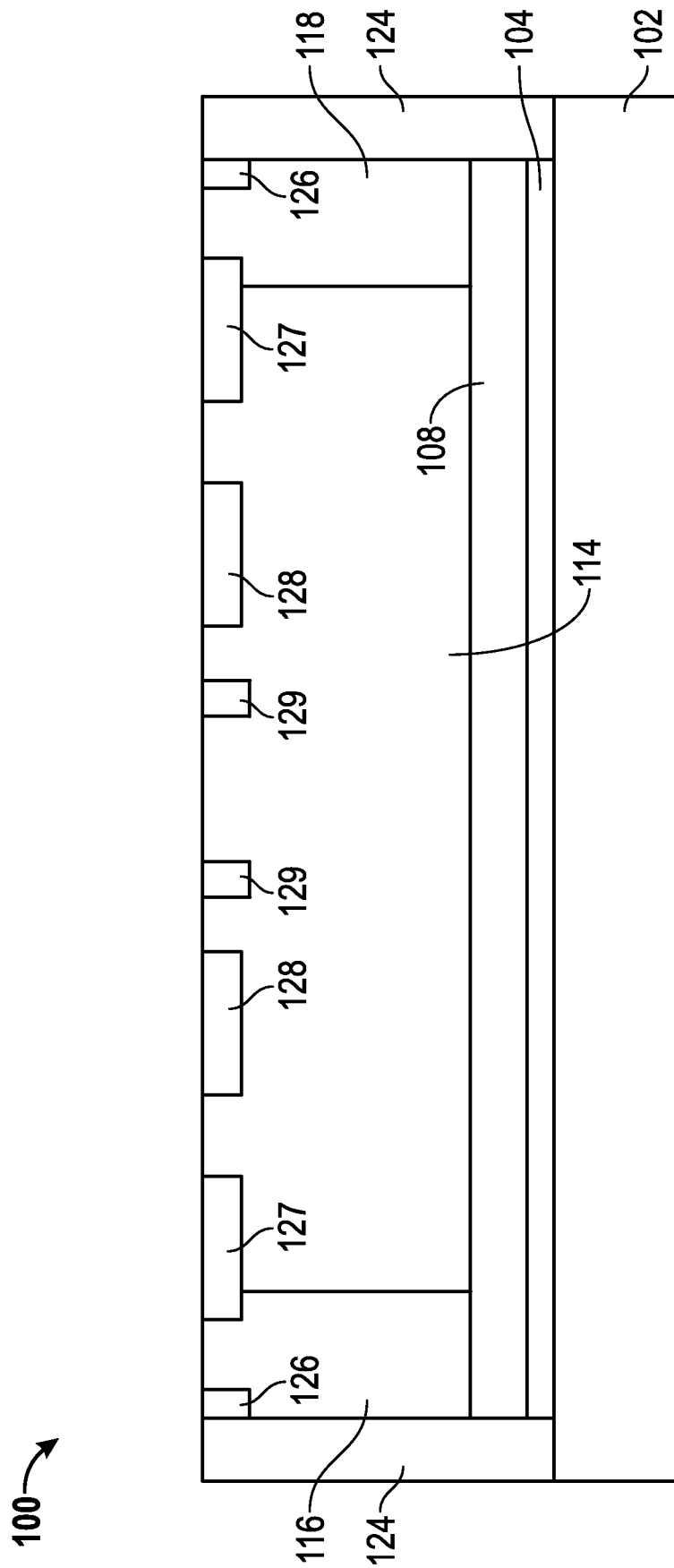


FIG. 5

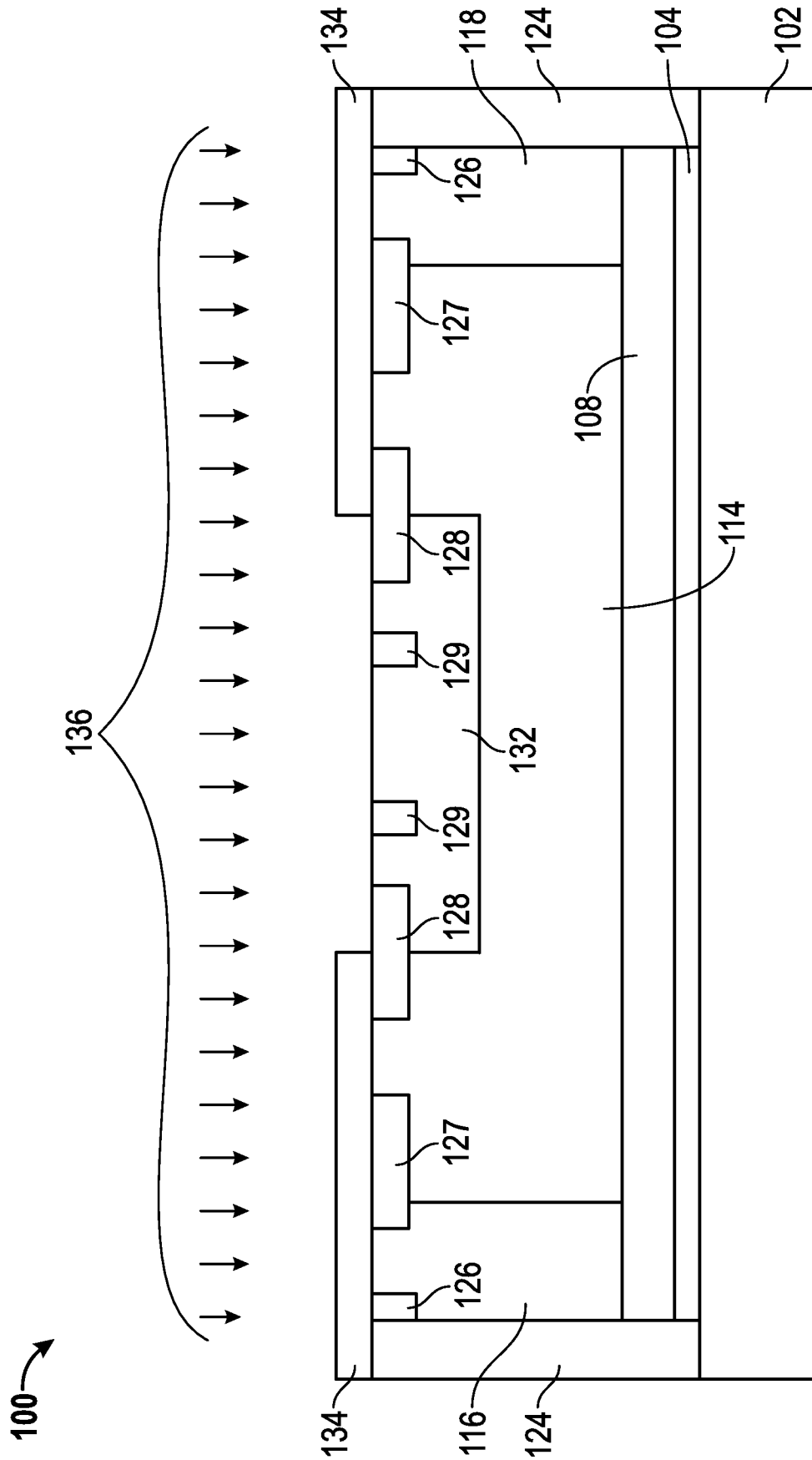


FIG. 6

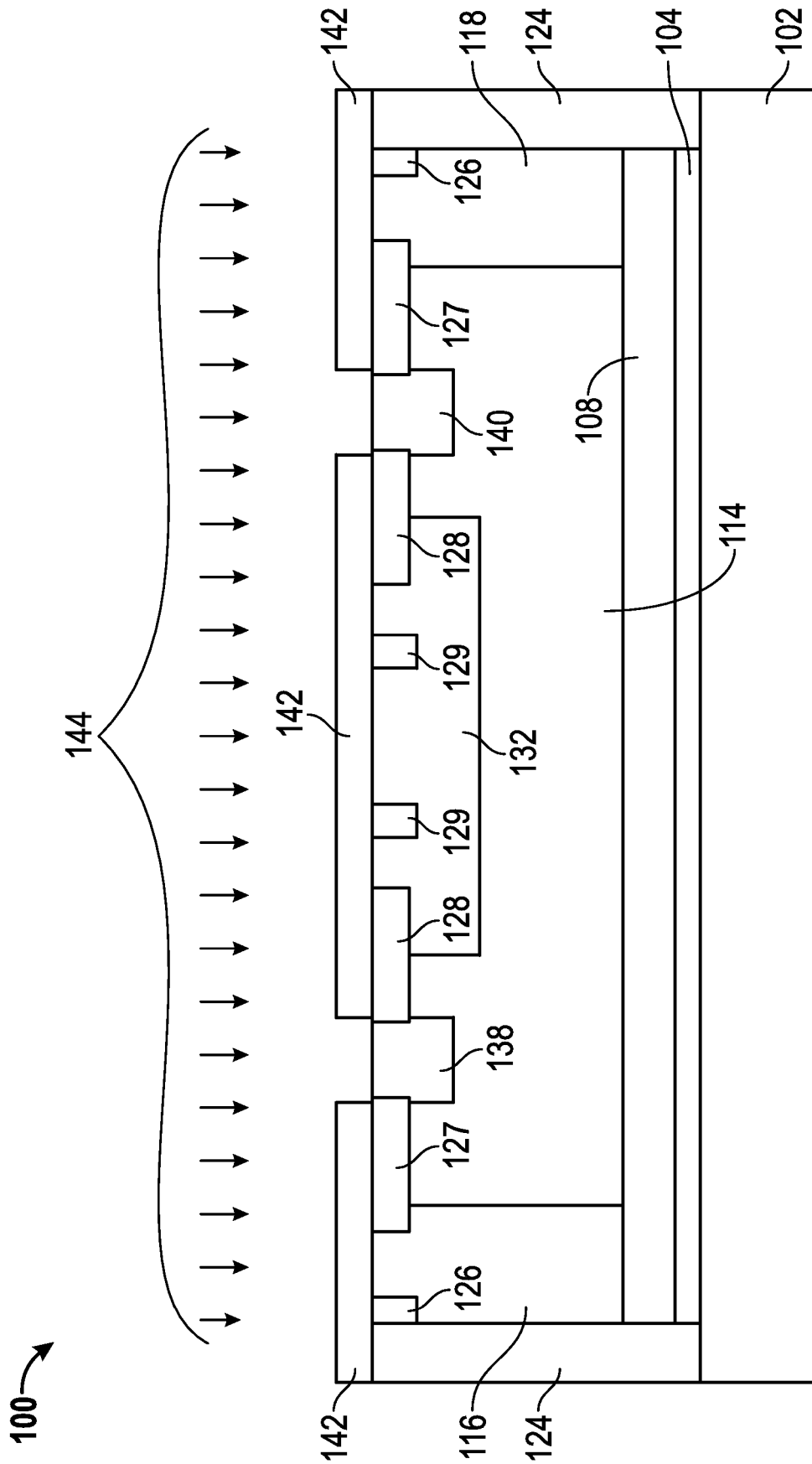


FIG. 7

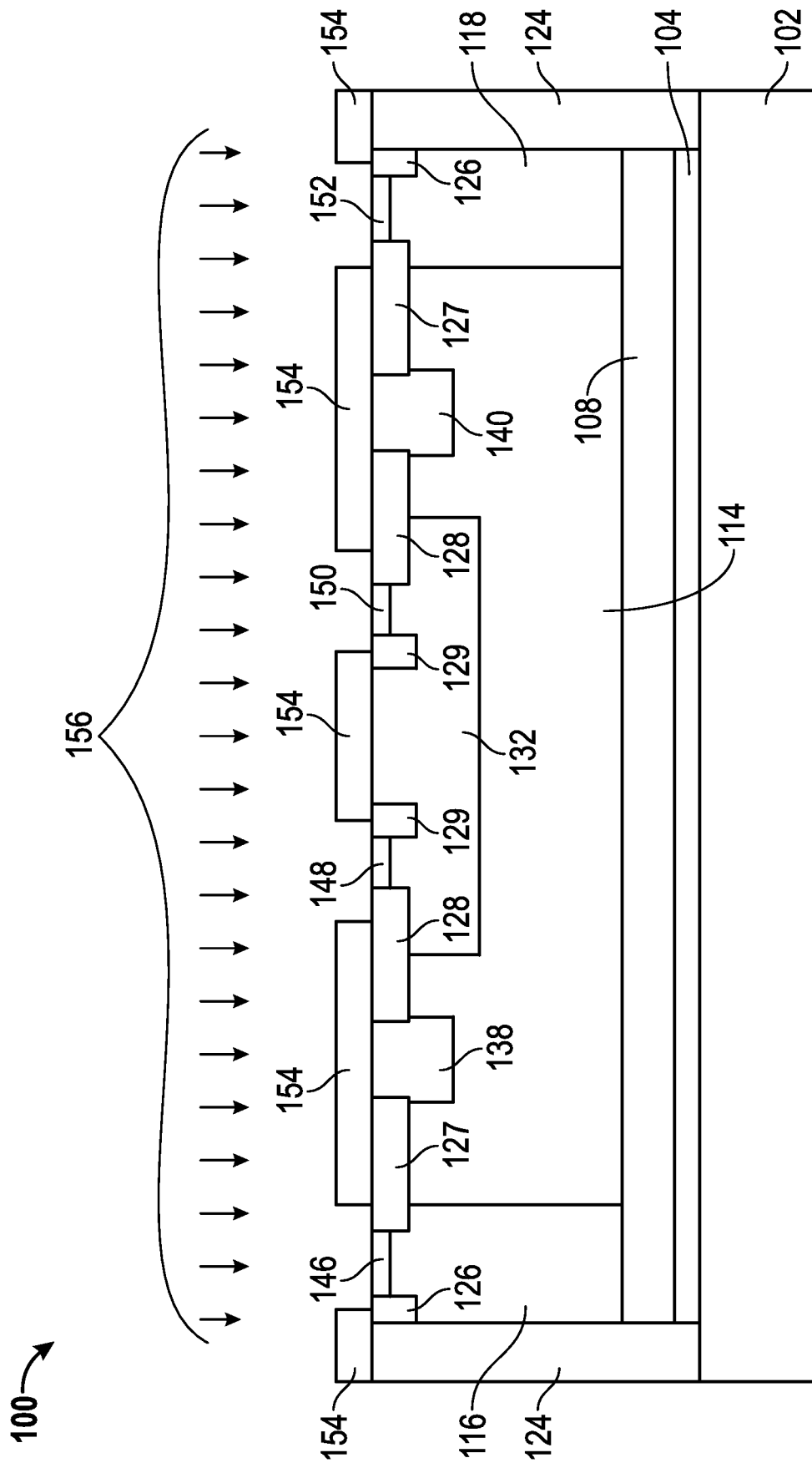
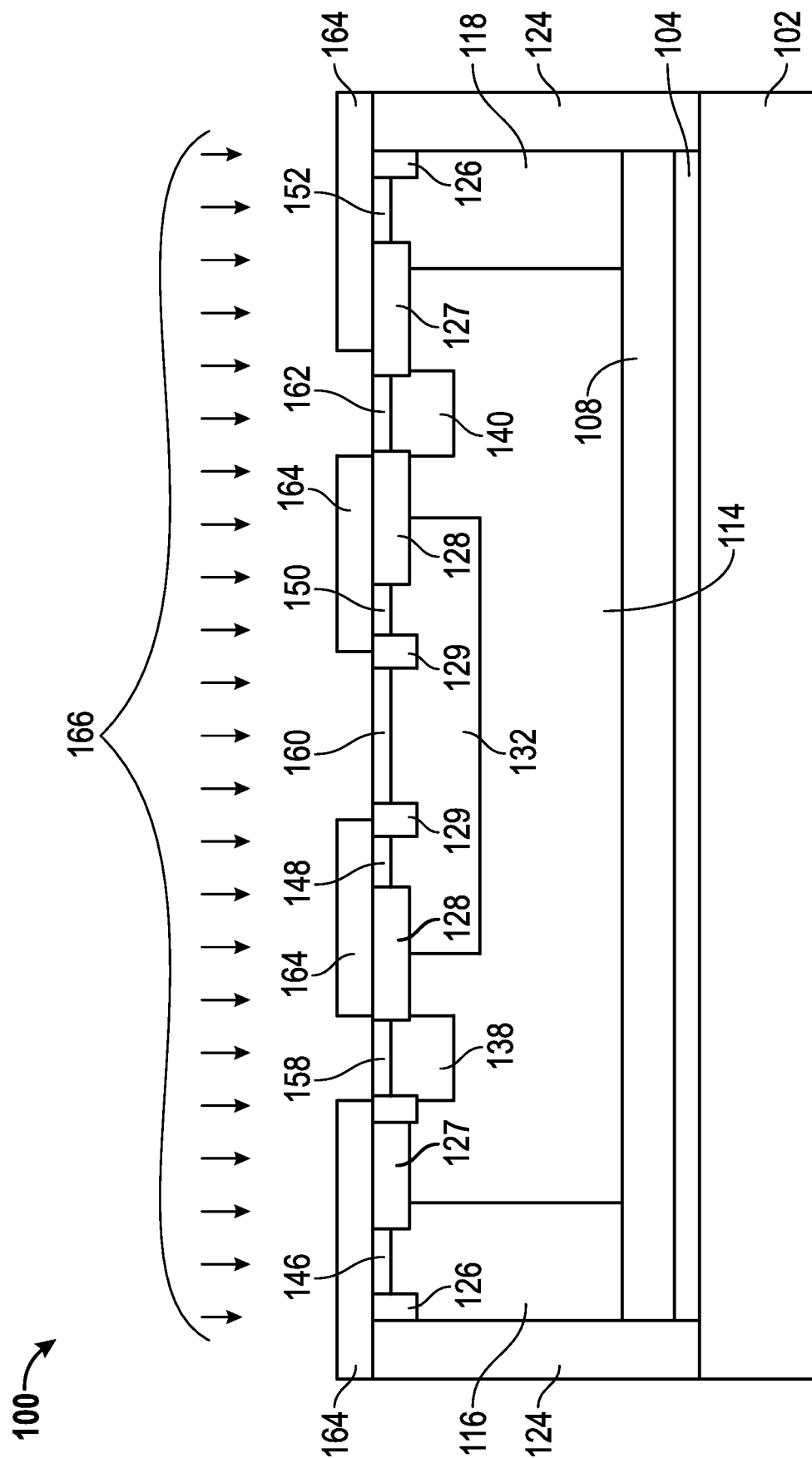


FIG. 8





**FIG. 9**

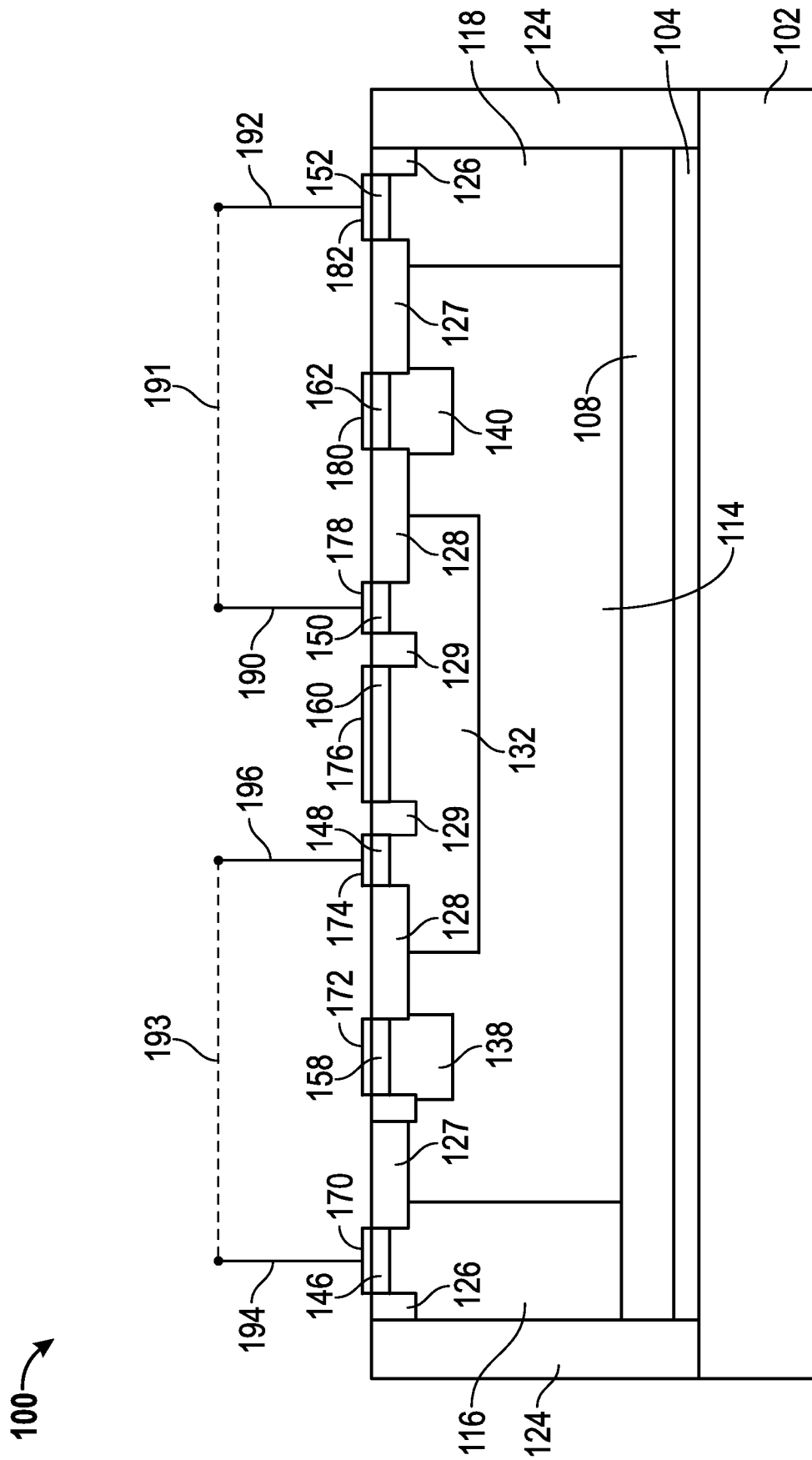


FIG. 10

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## SEMICONDUCTOR DEVICE AND RELATED FABRICATION METHODS

### RELATED APPLICATION

This application is a division U.S. patent application Ser. No. 13/773,432, filed Feb. 21, 2013.

### TECHNICAL FIELD

Embodiments of the subject matter described herein relate generally to semiconductor devices and methods for fabricating semiconductor devices, and more particularly, embodiments of the subject matter relate to methods for fabricating semiconductor devices having increased breakdown voltage and Early voltage.

### BACKGROUND

During normal operation, the voltage applied to a semiconductor device is constrained by the breakdown voltage of the device, which is the minimum applied voltage that causes avalanche breakdown in the device. For example, the rated voltage across terminals of transistor devices is typically set to a value that is well below the voltage that causes avalanche breakdown in the device to provide sufficient margin that accommodates manufacturing variations and/or transient voltage fluctuations. However, when numerous different types of semiconductor devices (e.g., diodes, field-effect transistors, bipolar junction transistors, and the like) are fabricated on a die or wafer as part of an integrated fabrication process, a breakdown voltage of a particular device may be compromised to achieve the desired performance for the other types of semiconductor devices. For example, a breakdown voltage of a bipolar transistor may be compromised as a result of the fabrication process being tailored to achieve desired on-resistances or breakdown voltages for field-effect transistors fabricated on the wafer. While additional or specialized fabrication process steps may be performed to improve the breakdown voltages or other device parameters, such additional fabrication process steps undesirably increase the cost and/or complexity of fabrication.

### BRIEF DESCRIPTION OF THE DRAWINGS

A more complete understanding of the subject matter may be derived by referring to the detailed description and claims when considered in conjunction with the following figures, wherein like reference numbers refer to similar elements throughout the figures, which are not necessarily drawn to scale.

FIGS. 1-10 illustrate, in cross section, a semiconductor device structure and exemplary methods for fabricating the semiconductor device in accordance with one embodiment of the invention.

### DETAILED DESCRIPTION

The following detailed description is merely illustrative in nature and is not intended to limit the embodiments of the subject matter or the application and uses of such embodiments. As used herein, the word "exemplary" means "serving as an example, instance, or illustration." Any implementation described herein as exemplary is not necessarily to be construed as preferred or advantageous over other implementations. Furthermore, there is no intention to be bound by any

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expressed or implied theory presented in the preceding technical field, background, or the following detailed description.

Embodiments of the subject matter described herein generally related to improved bipolar junction transistor structures that are capable of achieving relatively higher collector-to-emitter breakdown voltage and relatively higher Early voltage while being fabricated using process steps that may be optimized for fabricating other device structures (e.g., laterally diffused metal oxide semiconductor (LDMOS) field-effect transistors or other MOS transistors) concurrently fabricated on the same semiconductor substrate. As described in greater detail below, in exemplary embodiments, the collector region of the bipolar transistor structure is surrounded laterally by a doped sinker region of the opposite conductivity, and the doped sinker region is electrically connected to the base region, and therefore, has the same electrical potential of the base region. Additionally, the collector region overlies a buried region having the same conductivity as the base region and the doped sinker region, and the doped sinker region abuts or otherwise contacts the buried region. In this manner, the collector region is effectively surrounded by doped regions of the opposite conductivity, which are biased to the electrical potential (or voltage) of the base. Thus, as the electrical potential of the base is increased relative to the collector, the sinker region and the buried region cooperatively deplete or otherwise distribute a portion of the electrical potential of the collector laterally and vertically away from the base and/or emitter, so that portions of the collector region enclosed by the sinker regions and the buried region are more fully depleted.

In exemplary embodiments, the bipolar transistor is fabricated on a silicon-on-insulator (SOI) substrate, with the collector region being realized as a relatively lightly doped epitaxial layer that is formed on the relatively higher doped buried region. By virtue of the collector being more lightly doped than the surrounding regions (e.g., the base region, the buried region and the sinker regions), portions of the collector may be more fully depleted when the base is biased with a higher potential. As a result, the potential of the portions of the collector region beneath the emitter regions stops following the collector bias voltage, thus the base width modulation is reduced, which, in turn, results in a relatively higher Early voltage. In addition, the portions of the collector region closest to the emitter regions may be fully depleted before the punch-through between the emitter and the collector, resulting in a relatively higher collector-to-emitter breakdown voltage.

FIGS. 1-10 illustrate, in cross-section, methods for fabricating a semiconductor device structure **100** suitable for use as a bipolar transistor in accordance with exemplary embodiments. It should be appreciated that although the subject matter may be described herein in the context of a PNP bipolar transistor device, the subject matter is not intended to be limited to PNP bipolar transistor devices and may be implemented in an equivalent manner for an NPN bipolar transistor device (e.g., by interchanging the conductivities of the doped regions). Various steps in the manufacture of semiconductor devices are well known and so, in the interest of brevity, many conventional steps will only be mentioned briefly herein or will be omitted entirely without providing the well known process details. It should be noted that in some embodiments, the semiconductor device structure **100** may be rectangular, square, or circular in shape or otherwise formed so that the regions depicted as being separate in the cross-sections of FIGS. 1-10 may be integral or otherwise continuous, as will be appreciated in the art. Thus, the plural

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form “regions” may be used herein to describe regions that appear to be separate in the cross-section, but in practice, may be a single integral region.

Referring now to FIG. 1, in exemplary embodiments, fabrication of the semiconductor device structure 100 begins by providing or otherwise obtaining a substrate 101 of semiconductor material. In the illustrated embodiment, the fabrication process begins by obtaining a silicon-on-insulator (SOI) substrate 101 having a support (or handle) layer 102 of semiconductor material, an insulating layer 104 of dielectric material on the support layer 102, and a layer 106 of semiconductor material on the insulating layer 104. As described in greater detail below, in exemplary embodiments, the layer 106 of semiconductor material is utilized to epitaxially grow additional semiconductor material for subsequently fabricating one or more transistor devices thereon, and accordingly, for convenience, but without limitation, the layer 106 of semiconductor material may alternatively be referred to herein as the seed layer. In an exemplary embodiment, the semiconductor material of each of the layers 102, 106 is realized as a silicon material, wherein the term “silicon material” is used herein to encompass the relatively pure silicon materials typically used in the semiconductor industry as well as silicon admixed with other elements such as germanium, carbon, and the like. Alternatively, one or more of the layers 102, 106 may be realized as germanium, gallium arsenide, and the like, and/or one or more of the layers 102, 106 may include layers of different semiconductor materials. In accordance with one embodiment, the insulating layer 104 is realized as an oxide layer formed in a subsurface region of the semiconductor substrate 101, also known as a buried oxide (BOX) layer. For example, a buried oxide layer may be formed by oxidizing a wafer of semiconductor material (e.g., seed layer 106) which is then bonded to the support layer 102 to provide the insulating layer 104 of oxide material between the support layer 102 and the seed layer 106.

In exemplary embodiments, the support layer 102 and the seed layer 106 are each lightly doped. For example, the seed layer 106 may be realized as a P-type silicon material having a P-type dopant concentration (e.g., boron ions or a boron ionized species) in the range of about  $1 \times 10^{13}/\text{cm}^3$  to about  $1 \times 10^{17}/\text{cm}^3$ , and more particularly, about  $1 \times 10^{15}/\text{cm}^3$ . Similarly, the support layer 102 may also be doped with the same (or different) conductivity-determining impurity type as the seed layer 106. In exemplary embodiments, the support layer 102 is realized as an N-type silicon material having a N-type dopant concentration in the range of about  $1 \times 10^{13}/\text{cm}^3$  to about  $1 \times 10^{17}/\text{cm}^3$ , and more particularly, about  $1 \times 10^{15}/\text{cm}^3$ . It should be understood that the fabrication process described herein is not constrained by the substrate of semiconductor material utilized, and the fabrication process described herein may also be used to create devices from a bulk semiconductor substrate.

Referring to FIG. 2, in exemplary embodiments, fabrication of the semiconductor device structure 100 continues by masking peripheral portions of the semiconductor device structure 100 and forming a doped region 108 of semiconductor material within the seed layer 106 having a conductivity type that is opposite the conductivity of the seed layer 106. The doped region 108 is formed by masking the semiconductor device structure 100 with a masking material 110, such as a photoresist material, that is patterned to provide an implantation mask that exposes the interior portion of the seed layer 106 to be used for the doped region 108. The doped region 108 is then formed by implanting N-type ions, such as antimony ions and/or phosphorous ions, illustrated by arrows 112, in the seed layer 106 with a dopant concentration in the

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range of about  $1 \times 10^{16}/\text{cm}^3$ , to about  $1 \times 10^{20}/\text{cm}^3$ , and more particularly about  $1 \times 10^{19}/\text{cm}^3$ , and at an energy level in the range of about 50 kiloelectron volts (keV) to about 2000 keV. In the illustrated embodiment, the depth of the doped region 108 (after subsequent thermal annealing or any other diffusion) corresponds to the thickness of the seed layer 106 so that the doped region 108 extends to and abuts or otherwise contacts the insulating layer 104. For example, in accordance with one or more embodiments, the thickness of the seed layer 106 may be within the range of about 0.5 micrometer (or micron) to about 4 microns (depending on the needs of a particular application), such that the doped region 108 has a depth in the range of 0.5 micron to about 4 microns that corresponds to the thickness of the seed layer 106. It should be noted that the thickness of the doped region 108 is not constrained to the thickness of the seed layer 106 and may increase in thickness as a result of subsequent processing (e.g., up-diffusion during subsequent epitaxial growth).

Referring now to FIG. 3, after forming the doped region 108, fabrication of the semiconductor device structure 100 continues by removing the masking material 110 and forming or otherwise providing a doped region 114 of semiconductor material overlying the doped region 108 that has a conductivity type that is opposite that of the doped region 108. For example, a P-type epitaxial layer 114 may be formed by epitaxially growing silicon material on the seed layer 106 and in-situ doping the silicon material by adding boron ions (or other P-type ions) to the reactants used to epitaxially grow the layer 114. In one or more embodiments, the epitaxial layer 114 has a P-type dopant concentration in the range of about  $1 \times 10^{13}/\text{cm}^3$  to about  $1 \times 10^{16}/\text{cm}^3$ , and more particularly about  $1 \times 10^{15}/\text{cm}^3$ . In this regard, the dopant concentration of the epitaxial layer 114 is less than the dopant concentration of the doped region 108 by one or more orders of magnitude (e.g., by factor of ten or more). In an exemplary embodiment, the epitaxial layer 114 is grown to a thickness in the range of about 2 microns to about 9 microns, which may vary depending on the needs of a particular application. For example, in one embodiment, the seed layer 106 has a thickness of about 1.5 microns and the epitaxial layer 114 has a thickness of about 3 microns so that the resulting thickness of semiconductor material overlying the insulating layer 104 is about 4.5 microns. After formation of the epitaxial layer 114, the doped region 108 occupies a subsurface region of the semiconductor device structure 100, and accordingly, may alternatively be referred to herein as a buried region.

Turning now to FIG. 4, after forming the epitaxial layer 114, the fabrication process continues by masking the interior portion of the epitaxial layer 114 and forming doped sinker regions 116, 118 of semiconductor material having the opposite conductivity type within the epitaxial layer 114. It should be noted that although the cross-sectional view illustrates two doped sinker regions 116, 118, in practice, the sinker regions 116, 118 are integral and provide a contiguous or continuous doped sinker region about the periphery of the epitaxial layer 114 that circumscribes or otherwise laterally encloses the epitaxial layer 114. The sinker regions 116, 118 are formed by masking the semiconductor device structure 100 with a masking material 120 that is patterned to provide an implantation mask that exposes the peripheral portions of the epitaxial layer 114 to be used for the sinker regions 116, 118. For example, N-type sinker regions 116, 118 are formed by implanting N-type ions, such as phosphorous ions or arsenic ions, illustrated by arrows 122, in the epitaxial layer 114 with a dopant concentration in the range of about  $1 \times 10^{16}/\text{cm}^3$  to about  $1 \times 10^{19}/\text{cm}^3$ , and more particularly within the range of about  $1 \times 10^{17}/\text{cm}^3$  to about  $1 \times 10^{18}/\text{cm}^3$ . In this regard, the

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dopant concentration of the N-type sinker regions **116**, **118** is also greater than the dopant concentration of the P-type epitaxial layer **114**, and preferably, by one or more orders of magnitude. The ions are implanted at an energy level in the range of about 2000 keV to about 3000 keV to provide the N-type sinker regions **116**, **118** with a depth (after subsequent thermal annealing or any other diffusion) corresponding to the thickness of the epitaxial layer **114** so that the N-type sinker regions **116**, **118** extend to and abut or otherwise contact the N-type buried region **108**, thereby electrically connecting the N-type sinker regions **116**, **118** to the N-type buried region **108**.

Referring now to FIG. 5, the illustrated fabrication process by isolating the bipolar transistor structure from adjacent semiconductor devices by performing shallow trench isolation (STI) to form shallow isolation regions **126**, **127**, **128**, **129** of a dielectric material in the upper portions of the epitaxial layer **114** and performing deep trench isolation (DTI) to provide deep isolation regions **124** of a dielectric material in the lower portions of the epitaxial layer **114** that extend to the support layer **102**. As illustrated, the shallow isolation regions **126**, **127** may extend laterally into the upper portions of the N-type sinker regions **116**, **118** adjacent to subsequently formed deep isolation regions **124**. To form the shallow isolation regions **126**, **127**, **128**, **129**, the interior portion of the device structure **100** is masked with a masking material that is patterned to expose portions of the epitaxial layer **114**, which are then etched to a desired depth (which is less than the thickness of the epitaxial layer **114**), and a dielectric material, such as an oxide material, may be deposited to fill the trenches, resulting in shallow isolation regions **126**, **127**, **128**, **129**. In accordance with one or more exemplary embodiments, the depth of the shallow isolation regions **126**, **127**, **128**, **129** is in the range of about 0.05 microns to about 1 micron, and more preferably, within the range of 0.2 microns to 0.5 microns. The shallow isolation regions **126**, **127**, **128**, **129** help define the lateral boundaries of subsequently formed shallow contact regions and/or the electrode contacts formed thereon, as described in greater detail below in the context of FIGS. 8-10. After forming shallow isolation regions **126**, **127**, **128**, **129**, the fabrication process continues by performing DTI to provide deep isolation regions **124**. For example, to form deep isolation regions **124**, the interior of the semiconductor device structure **100** is masked with a masking material that is subsequently patterned to expose the peripheral portions of the epitaxial layer **114** and seed layer **106**, which are then etched until the insulating layer **104** is etched through, and thereafter, a dielectric material, such as an oxide material, may be deposited in the trenches or grown on exposed surfaces of the trenches to fill the trenches. Although not illustrated in FIG. 5, in some embodiments, an inner conductive material, such as a doped polysilicon material, may be formed in the interior or central portion of the deep isolation regions **124** to facilitate an electrical connection to the support layer **102**. The deep isolation regions **124** are integral and provide a contiguous or continuous isolation region that circumscribes or otherwise laterally encloses the bipolar transistor structure to isolate the bipolar transistor structure from adjacent semiconductor devices fabricated on the same semiconductor substrate.

Turning now to FIG. 6, in the illustrated embodiment, the fabrication process continues by forming a well region **132** having a conductivity type that is opposite the conductivity of the epitaxial layer **114** within an interior portion of the epitaxial layer **114**. In this regard, the well region **132** functions as the base region of the bipolar transistor structure while the surrounding P-type epitaxial layer **114** functions as the col-

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lector region of the bipolar transistor structure. For the illustrated embodiment, fabrication of the N-type base region **132** is achieved by masking the semiconductor device structure **100** with a masking material **134** that is patterned to provide an implantation mask that exposes the central portion of the epitaxial layer **114**. As illustrated, the remaining masking material **134** masks the N-type sinker regions **116**, **118** and the peripheral portions of the epitaxial layer **114** to physically isolate or otherwise separate the base region **132** from the sinker regions **116**, **118**. In this regard, the base region **132** does not physically contact the sinker regions **116**, **118**. The N-type base region **132** is then formed by implanting N-type ions, such as phosphorous ions or arsenic ions, illustrated by arrows **136**, into the central portion of the P-type epitaxial layer **114** with a dopant concentration that is greater than the dopant concentration of the P-type epitaxial layer **114**, preferably within the range of about  $1 \times 10^{16}/\text{cm}^3$  to about  $1 \times 10^{18}/\text{cm}^3$ . In this regard, the dopant concentration of the base region **132** may be one or more orders of magnitude greater than the dopant concentration of the P-type epitaxial layer **114**. In one embodiment, the dopant concentration of the base region **132** is less than the dopant concentration of the sinker regions **116**, **118**. In exemplary embodiments, the ions **136** are implanted at an energy level in the range of about 250 keV to about 2000 keV to provide the N-type base region **132** with a depth (after subsequent thermal annealing or any other diffusion) that is less than the thickness of the epitaxial layer **114** so that a portion of the P-type epitaxial layer **114** remains underneath the N-type base region **132** between the base region **132** and the buried region **108** to physically isolate or otherwise separate the base region **132** from the buried region **108**. In this regard, the base region **132** does not physically contact the buried region **108**. In accordance with one or more exemplary embodiments, the depth of the N-type base region **132** is in the range of about 0.5 microns to about 2 microns. In one embodiment, the thickness of the portion of the epitaxial layer **114** beneath the base region **132** is about 1 micron.

After formation of the N-type base region **132**, the remaining region of P-type epitaxial layer **114** that functions as the collector is bordered by (and effectively surrounded or otherwise enclosed by) regions having the opposite conductivity type (e.g., N-type regions **108**, **116**, **118**, **132**) and a greater dopant concentration than that of the P-type epitaxial layer **114** that makes up the collector region. As described in greater detail below in the context of FIG. 10, by virtue of the higher dopant concentration of the surrounding regions, the portions of the collector region **114** surrounded by the base region **132**, the sinker regions **116**, **118** and the buried region **108** may be more fully depleted as the electrical potential of the base is increased.

Turning now to FIG. 7, in the illustrated embodiment, fabrication of the device structure **100** continues by masking the N-type regions **116**, **118**, **132** and forming P-type well regions **138**, **140** in portions of the P-type epitaxial layer **114** between the N-type base region **132** and the N-type sinker regions **116**, **118**. To fabricate P-well regions **138**, **140**, the semiconductor device structure **100** is masked with a masking material **142** that is patterned to provide an implantation mask that exposes portions of the P-type epitaxial region **114** between the N-type base region **132** and the surrounding N-type sinker regions **116**, **118** while masking the N-type regions **116**, **118**, **132** and the portions of the P-type epitaxial region **114** adjacent to the N-type regions **116**, **118**, **132**. The P-well regions **138**, **140** are then formed by implanting P-type ions, such as boron ions, illustrated by arrows **144**, in the exposed interior portions of the epitaxial layer **114** with a dopant concentration that is greater than the dopant concen-

tration of the P-type epitaxial layer **114**, preferably within the range of  $1 \times 10^{16}/\text{cm}^3$  to about  $1 \times 10^{19}/\text{cm}^3$ , and at an energy level in the range of about 100 keV to about 500 keV to provide the P-well regions **138**, **140** with a depth (after subsequent thermal annealing or any other diffusion) that may be less than the thickness of the epitaxial layer **114**. In one embodiment, a portion of the lighter doped P-type epitaxial layer **114** remains vertically between the P-well regions **138**, **140** and the N-type buried region **108** to sustain a high vertical breakdown voltage between the collector and the buried region **108**. The P-well regions **138**, **140** function as a relatively higher doped portion of the collector to lower the collector resistance. Again, it is noted that although the cross-sectional view illustrates two P-well regions **138**, **140**, in practice, the P-well regions **138**, **140** may be integral and provide a contiguous or continuous region. Additionally, although FIG. 7 depicts the depth of the P-well regions **138**, **140** having a depth that is less than a depth of the base region **132**, in practice, the depth of the P-well regions **138**, **140** may vary to suit the needs of a particular application.

Referring now to FIGS. 8-9, after forming the P-well regions **138**, **140**, the fabrication process continues by appropriately masking the semiconductor device structure **100**, forming shallow N-type regions **146**, **148**, **150**, **152** within the N-type sinker regions **116**, **118** and base region **132** and forming shallow P-type regions **158**, **160**, **162** within the P-well regions **138**, **140** and the N-type base region **132**. In this regard, the shallow P-type region **160** within the base region **132** functions as the emitter of the bipolar transistor, while P-type regions **158**, **162** function as contact regions for the collector. N-type regions **148**, **150** function as contact regions for the base, and N-type regions **146**, **152** function as contact regions for the sinker regions **116**, **118**. Again, it is noted that in practice, the N-type sinker contact regions **146**, **152**, the N-type base contact regions **148**, **150**, and the P-type collector contact regions **158**, **162** may each be realized as an integral or contiguous doped region. Additionally, although not illustrated in FIGS. 8-9, practical embodiments of the fabrication process may also include the formation of relatively lighter doped extension regions for the emitter region **160**.

As illustrated in FIG. 8, the shallow N-type contact regions **146**, **148**, **150**, **152** are formed by masking the semiconductor device structure **100** with a masking material **154** that is patterned to expose the N-type sinker regions **116**, **118** and portions of the base region **132** that are spaced apart from the lateral boundaries between the base region **132** and the P-type epitaxial region **114**. The shallow N-type contact regions **146**, **148**, **150**, **152** are then formed by implanting N-type ions, such as phosphorous ions or arsenic ions, illustrated by arrows **156**, in the exposed portions of the N-type regions **116**, **118**, **132** with a dopant concentration in the range of about  $1 \times 10^{19}/\text{cm}^3$  to about  $1 \times 10^{21}/\text{cm}^3$  and at an energy level in the range of about 20 keV to about 100 keV to provide the N-type contact regions **146**, **148**, **150**, **152** with a depth (after diffusion) that is less than a depth of the shallow isolation regions **126**, **127**, **128**, **129**. For example, in accordance with one or more embodiments, the depth of the shallow N-type contact regions **146**, **148**, **150**, **152** is in the range of about 0.05 microns to about 0.3 microns.

Referring to FIG. 9, in a similar manner, the shallow P-type regions **158**, **160**, **162**, are formed by masking the semiconductor device structure **100** with a masking material **164** that is patterned to expose the P-well regions **138**, **140** and the central portion of the N-type base region **132** surrounded by the shallow isolation region **129**. After the masking material **164** is patterned, the shallow P-type contact regions **158**, **160**,

**162** are formed by implanting P-type ions, such as boron ions, illustrated by arrows **166**, in the exposed portions of the P-well regions **138**, **140** and the N-type base region **132** with a dopant concentration in the range of about  $1 \times 10^{19}/\text{cm}^3$  to about  $1 \times 10^{21}/\text{cm}^3$  and at an energy level in the range of about 2 keV to about 50 keV to provide the P-type contact regions **158**, **160**, **162** with a depth (after diffusion) that is less than a depth of the shallow isolation regions **126**, **127**, **128**, **129** (e.g., in the range of about 0.05 microns to about 0.3 microns). Thereafter, the masking material **164** is removed.

Turning now to FIG. 10, in the illustrated embodiment, after the shallow contact regions are formed, fabrication of the device structure **100** continues by forming contacts **170**, **172**, **174**, **176**, **178**, **180**, **182** overlying the contact regions **146**, **158**, **148**, **160**, **150**, **162**, **152**. In an exemplary embodiment, the contacts **170**, **172**, **174**, **176**, **178**, **180**, **182** are realized as a metal silicide layer formed by conformably depositing a layer of silicide-forming metal onto the exposed surfaces of the contact regions **146**, **158**, **148**, **160**, **150**, **162**, **152**, and the device structure **100** is then heated, for example by RTA, to react the silicide-forming metal with the exposed silicon and form a metal silicide layer **170**, **172**, **174**, **176**, **178**, **180**, **182** at the top of each contact region **146**, **158**, **148**, **160**, **150**, **162**, **152**. Any silicide-forming metal that is not in contact with exposed silicon, such as, for example, the silicide-forming metal that is deposited on the isolation regions **126**, **127**, **128**, **129** does not react during the RTA to form a silicide and may subsequently be removed in a conventional manner.

In accordance with one or more embodiments, after forming silicide contacts, fabrication of the device structure **100** continues by forming appropriate electrical interfaces and/or electrical connections to/from the silicide contacts, for example, using subsequently formed interconnect layers overlying the semiconductor device structure **100**. In exemplary embodiments, the N-type sinker regions **116**, **118** are electrically connected (or shorted) to the N-type base region **132**, for example, by providing a conductive connection **193**, **191** between a base contact **174**, **178** and a sinker contact **170**, **182**. For example, terminals **190**, **192**, **194**, **196**, such as contact plugs or the like, may be formed overlying the contacts **178**, **182**, **170**, **174**, and a connection **191**, **193** may be provided between the terminals **190**, **192**, **194**, **196**, for example, by forming the connection **191**, **193** using a conductive trace in an overlying metal interconnect layer. In this manner, the sinker regions **116**, **118** and the buried region **108** are effectively biased to the same electrical potential (or voltage) as the base region **132**.

One benefit of the semiconductor device structure **100** depicted in FIG. 10 is that when a voltage applied to the base electrode (e.g., at contact **174** and **178**) exceeds the voltage (or electrical potential) of the collector electrode, portions of the collector are depleted laterally away from the base region **132** by the N-type sinker regions **116**, **118** and vertically away from the base region **132** by the buried region **108**. By virtue of the N-type regions **108**, **116**, **118** surrounding the collector region **114** and the base region **132** having a higher dopant concentration than the collector region **114**, the collector region between the collector contact and the base contact may be fully depleted when the base is biased with a high voltage. Upon the depletion, the potential of the collector region below the emitter is effectively fixed at a certain value. As a result, Early voltage for the bipolar transistor device is significantly improved (e.g., increased). Additionally, by virtue of depletion of lightly doped collector before the punch-through between the emitter and collector, the breakdown between the emitter and the collector takes place outside the active bipolar

region, giving nearly identical values for the collector-emitter breakdown voltage and the collector-base breakdown voltage. Accordingly, the high-side capability of the bipolar transistor device is improved.

For the sake of brevity, conventional techniques related to semiconductor and/or integrated circuit fabrication, bipolar transistors, biasing, and other functional aspects of the subject matter may not be described in detail herein. In addition, certain terminology may also be used herein for the purpose of reference only, and thus are not intended to be limiting. For example, the terms “first”, “second” and other such numerical terms referring to structures do not imply a sequence or order unless clearly indicated by the context.

In conclusion, systems, devices, and methods configured in accordance with example embodiments of the invention relate to:

An apparatus is provided for a semiconductor device. The semiconductor device comprises a collector region of semiconductor material having a first conductivity type, a base region of semiconductor material within the collector region, the base region having a second conductivity type opposite the first conductivity type, and a first doped region of semiconductor material having the second conductivity type, wherein the first doped region is electrically connected to the base region and the collector region resides between the base region and the first doped region. In one or more embodiments, a dopant concentration of the first doped region is greater than a dopant concentration of the collector region, and the collector region overlies the first doped region. In one embodiment, the dopant concentration of the first doped region is at least ten times greater than the dopant concentration of the collector region. In another embodiment, the collector region comprises an epitaxial layer overlying the first doped region. In accordance with one embodiment, the semiconductor device further comprises a support layer of semiconductor material, a buried layer of dielectric material overlying the support layer, and a second doped region of semiconductor material overlying the buried layer, wherein the collector region overlies the second doped region. In one or more further embodiments, the first doped region abuts the second doped region, wherein a dopant concentration of the first doped region is greater than a dopant concentration of the collector region and a dopant concentration of the second doped region is greater than the dopant concentration of the collector region. In accordance with yet another embodiment, the first doped region and the base region are physically isolated by the collector region.

In another exemplary embodiment, a method of fabricating a bipolar transistor on a semiconductor substrate is provided. The method comprises forming a first region of semiconductor material having a first conductivity type in the semiconductor substrate, forming a collector region of semiconductor material having a second conductivity type opposite the first conductivity type overlying the first region, forming a second region of semiconductor material having the first conductivity type that abuts the first region, forming a base region of semiconductor material having the first conductivity type within the collector region of semiconductor material, and providing an electrical connection between the base region and the second region. In one embodiment, forming the collector region comprises forming an epitaxial layer of semiconductor material having the second conductivity type on the first region and forming the second region comprises implanting ions having the first conductivity type and a dopant concentration greater than a dopant concentration of the epitaxial layer into the epitaxial layer. In another embodiment, the semiconductor substrate comprises a silicon-on-

insulator substrate including a layer of semiconductor material overlying an insulating layer, wherein forming the first region comprises implanting ions having the first conductivity type into the layer of semiconductor material, and forming the collector region comprises forming an epitaxial layer of semiconductor material having the second conductivity type on the first region. In one embodiment, forming the epitaxial layer of semiconductor material comprises epitaxially growing in-situ doped semiconductor material having a dopant concentration that is less than a dopant concentration of the first region on the first region. In a further embodiment, forming the second region comprises implanting ions having the first conductivity type and a dopant concentration greater than the dopant concentration of the epitaxial layer into the epitaxial layer.

An apparatus for a bipolar transistor is provided in another exemplary embodiment. The bipolar transistor comprises a buried region having a first conductivity type, a collector region overlying the buried region, the collector region having a second conductivity type opposite the first conductivity type, a base region within the collector region, the base region having the first conductivity type, wherein at least a first portion of the collector region resides between the base region and the buried region, and a sinker region having the first conductivity type, wherein the sinker region abuts the buried region, at least a second portion of the collector region resides between the sinker region and the base region, and the sinker region is electrically connected to the base region. In one or more embodiments, the sinker region laterally surrounds the collector region. In another embodiment, a dopant concentration of the collector region is less than a dopant concentration of the buried region, wherein the dopant concentration of the collector region is less than a dopant concentration of the sinker region. In another embodiment, the dopant concentration of the collector region is less than a dopant concentration of the sinker region. In yet another embodiment, the bipolar transistor includes an emitter region within the base region, wherein the emitter region has the second conductivity.

While at least one exemplary embodiment has been presented in the foregoing detailed description, it should be appreciated that a vast number of variations exist. It should also be appreciated that the exemplary embodiment or embodiments described herein are not intended to limit the scope, applicability, or configuration of the claimed subject matter in any way. Rather, the foregoing detailed description will provide those skilled in the art with a convenient road map for implementing the described embodiment or embodiments. It should be understood that various changes can be made in the function and arrangement of elements without departing from the scope defined by the claims, which includes known equivalents and foreseeable equivalents at the time of filing this patent application. Accordingly, details of the exemplary embodiments or other limitations described above should not be read into the claims absent a clear intention to the contrary.

What is claimed is:

1. A method of fabricating a bipolar transistor on a semiconductor substrate, the method comprising:
  - forming a first region of semiconductor material having a first conductivity type in the semiconductor substrate;
  - forming a collector region of semiconductor material having a second conductivity type opposite the first conductivity type overlying the first region;
  - forming a second region of semiconductor material having the first conductivity type that abuts the first region;

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forming a base region of semiconductor material having the first conductivity type within the collector region of semiconductor material; and

providing an electrical connection between the base region and the second region, the electrical connection resulting in the base region and the second region having the same electrical potential.

2. The method of claim 1, wherein forming the collector region comprises forming the collector region having a dopant concentration that is less than a dopant concentration of the first region.

3. The method of claim 1, wherein a dopant concentration of the first region is greater than a dopant concentration of the collector region.

4. The method of claim 1, the semiconductor substrate comprising a support layer of semiconductor material, a buried layer of dielectric material overlying the support layer, and a second layer of semiconductor material overlying the buried layer, wherein forming the first region comprises forming the first region in the second layer.

5. The method of claim 1, wherein:

forming the collector region comprises forming an epitaxial layer of semiconductor material having the second conductivity type on the first region; and

forming the second region comprises implanting, into the epitaxial layer, ions having the first conductivity type and a dopant concentration greater than a dopant concentration of the epitaxial layer.

6. The method of claim 1, the semiconductor substrate comprising a silicon-on-insulator substrate including a layer of semiconductor material overlying an insulating layer, wherein:

forming the first region comprises implanting ions having the first conductivity type into the layer of semiconductor material; and

forming the collector region comprises forming an epitaxial layer of semiconductor material having the second conductivity type on the first region.

7. The method of claim 6, wherein forming the epitaxial layer of semiconductor material comprises epitaxially growing, on the first region, in-situ doped semiconductor material having a dopant concentration that is less than a dopant concentration of the first region.

8. The method of claim 7, wherein forming the second region comprises implanting, into the epitaxial layer, ions having the first conductivity type and a dopant concentration greater than the dopant concentration of the epitaxial layer.

9. A method of fabricating a bipolar transistor on a semiconductor substrate, the method comprising:

forming a buried region having a first conductivity type in the semiconductor substrate;

forming a collector region overlying the buried region, the collector region having a second conductivity type opposite the first conductivity type;

forming a base region within the collector region, the base region having the first conductivity type, wherein at least a first portion of the collector region resides between the base region and the buried region; and

forming a sinker region having the first conductivity type in the semiconductor substrate, wherein:

the sinker region abuts the buried region; and

at least a second portion of the collector region resides between the sinker region and the base region; and

providing an electrical connection between the base region and the sinker region, the electrical connection resulting in the base region and the sinker region having the same electrical potential.

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10. The method of claim 9, wherein forming the sinker region comprises forming the sinker region laterally surrounding the collector region.

11. The method of claim 9, wherein forming the collector region comprises forming the collector region having a dopant concentration that is less than a dopant concentration of the buried region within the buried region.

12. The method of claim 11, wherein forming the collector region comprises forming the collector region having the dopant concentration that is less than a dopant concentration of the sinker region.

13. The method of claim 9, wherein:

forming the collector region comprises implanting ions having the second conductivity type and a first dopant concentration into the layer of semiconductor material; and

forming the sinker region comprises implanting ions having the first conductivity type and a second dopant concentration into the semiconductor substrate, wherein the first dopant concentration is less than the second dopant concentration.

14. The method of claim 9, further comprising forming an emitter region having the second conductivity type within the base region.

15. A method of fabricating a semiconductor device on a semiconductor substrate, the method comprising:

forming a first region of semiconductor material having a first conductivity type in the semiconductor substrate;

forming a collector region having a second conductivity type overlying the first region, the second conductivity type being opposite the first conductivity type;

forming a sinker region laterally surrounding the collector region and abutting the first region in the semiconductor substrate, the sinker region having the first conductivity type;

forming a base region having the first conductivity type within the collector region, at least a first portion of the collector region residing between the sinker region and the base region and at least a second portion of the collector region residing between the base region and the first region;

forming an emitter region having the second conductivity type within the base region; and

providing an electrical connection between the base region and the sinker region, the electrical connection resulting in the base region and the sinker region having the same electrical potential.

16. The method of claim 15, wherein:

forming the collector region comprises forming an epitaxial layer of semiconductor material having the second conductivity type on the first region; and

forming the sinker region comprises implanting, into the epitaxial layer, ions having the first conductivity type and a dopant concentration greater than a dopant concentration of the epitaxial layer.

17. The method of claim 15, the semiconductor substrate comprising a silicon-on-insulator substrate including a layer of semiconductor material overlying an insulating layer, wherein:

forming the first region comprises implanting ions having the first conductivity type into the layer of semiconductor material; and

forming the collector region comprises forming an epitaxial layer of semiconductor material having the second conductivity type on the first region.

18. The method of claim 17, wherein forming the epitaxial layer of semiconductor material comprises epitaxially grow-



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ing, on the first region, in-situ doped semiconductor material having a dopant concentration that is less than a dopant concentration of the first region.

**19.** The method of claim **18**, wherein forming the second region comprises implanting, into the epitaxial layer, ions 5 having the first conductivity type and a dopant concentration greater than the dopant concentration of the epitaxial layer.

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